RNATIONAL SEARCH REPORT

intermonal Application No PCT/EP2004/014219

A. CLASSIFICATION OF SUBJECT MATTER IPC 7 G03F7/20

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Mmmum documentation searched (classification system followed by classification symbols) $IPC\ 7\ G03F$

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal

Category °	Citation of document, with indication, where appropriate, of the relevant passages	Retevant to claim No.
A	US 2003/174408 A1 (ROSTALSKI HANS-JUERGEN ET AL) 18 September 2003 (2003-09-18) paragraphs '0025!, '0057!; table 1	1-24
A	HOFFNAGLE J A ET AL: "Liquid immersion deep-ultraviolet interferometric lithography" JOURNAL OF VACUUM SCIENCE & TECHNOLOGY B: MICROELECTRONICS PROCESSING AND PHENOMENA, AMERICAN VACUUM SOCIETY, NEW YORK, NY, US, vol. 17, no. 6, November 1999 (1999-11), pages 3306-3309, XP012007924 ISSN: 0734-211X page 3307 - page 3308 NA=1.2, n(prism) = 1.5 < n(immersion) = 1.51	1

X Palent family members are listed in annex
 "I" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention. "X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone. "Y" document of particular relevance, the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art. "&" document member of the same patent family
Date of mailing of the international search report
10/06/2005
Authorized officer Eisner, K

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Intelligional Application No PCT/EP2004/014219

Category* Citation of document, with indication, where appropriate, of the relevant passages P,X BRUCE SMITH: "Water-based 193nm immersion lithography" 'Online! 28 January 2004 (2004-01-28), XP002329291 Retrieved from the Internet: URL:http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20RIT%20microstepper%20efforts_Smith. pdf> 'retrieved on 2005-05-24! page 14: NA > 1, lens material: Si02 page 22: n(liquid lens) > 1.6 > n(Si02)	Relevant to claim No		
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Information on patent family members

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PCT/EP2004/014219

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